

Large area quantum capacitance limited graphene field effect transistors for high precision sensing

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Outline

- Growing need for high precision potentiometric sensors
- Graphene Ion Sensing Field Effect Transistors (ISFETs)
- Graphene ISFET model and the key parameters for optimizing SNR
- Improving pH detection limit by 20 times over the state-of-the-art
- I. Fakh, F. Mahvash, M. Siaj, T. Szkopek, Phys. Rev. Appl. 8 (2017) 044022



Importance of Water Quality

- Water is fundamental for existence of all living species on the planet





Limitations of current pH sensors

- Spectrophotometers are large and expensive
- Potentiometric sensors detection limit: 2 mpH
- Thermodynamically limited response to pH
- Noise (charge fluctuation, Johnson etc.)



17.5 mm



	Detection Limit	Price	Active Area
Spectrophotometry	0.1 mpH	> \$10,000	
Silicon ISFET	2 mpH	\$150 - \$200	~ μm
Glass Electrode	5 mpH	\$300 - \$500	~ mm

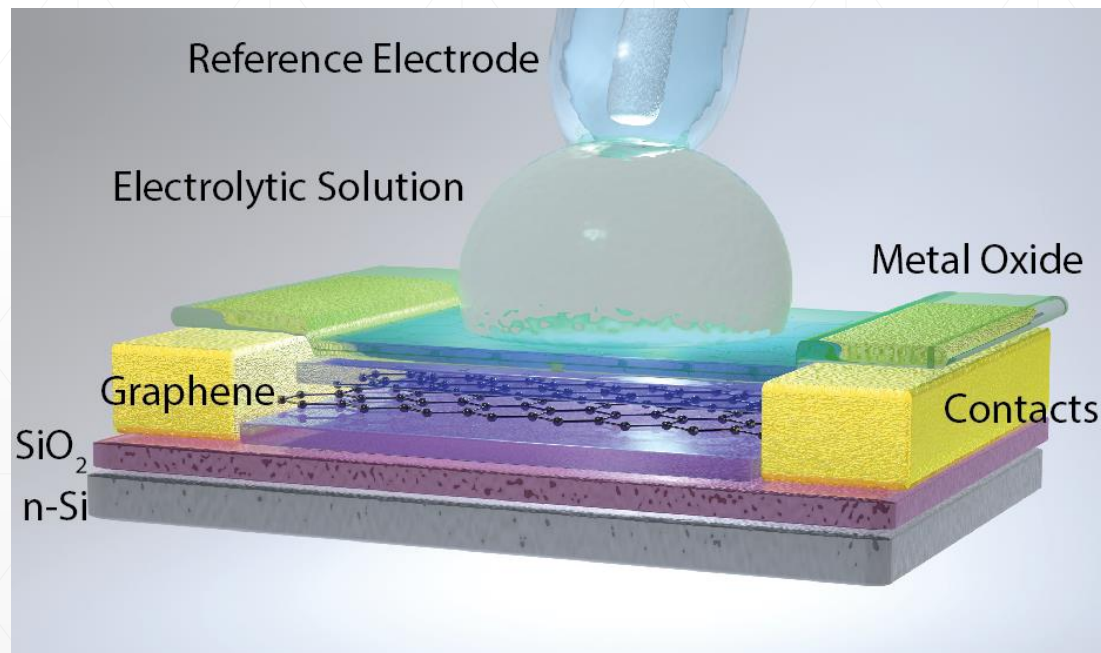
J. Rothberg et al. "An integrated semiconductor device enabling non-optical genome sequencing," Nature 475, 348–352 (2011).

http://www.coleparmer.ca/Product/Hach_9316900_Replacement_Sensor_for_95941_02_04_06/RK-95941-52

<https://www.thermofisher.com/ca/en/home/life-science/lab-equipment/ph-ion-conductivity-oxygen-measurement/ph-measurement/ph-electrodes.html>

Why Graphene FETs for sensing?

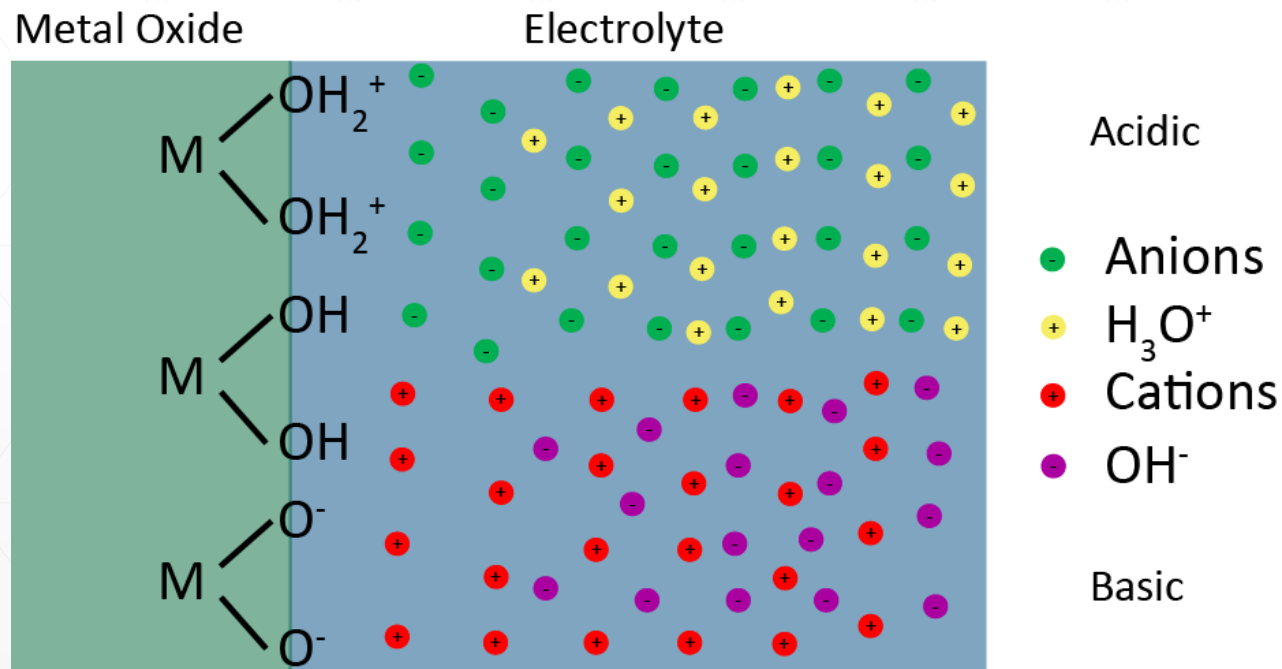
- Coupling between the charge carriers and surface potential
- Low Johnson noise
- Relatively inexpensive fabrication process
- High field effect mobility





Why metal oxides?

- Surface hydroxyl groups will protonate or deprotonate.
- In the 1970s, Bergveld discovered that metal oxides have an intrinsic buffering capacity





The Nernst limit

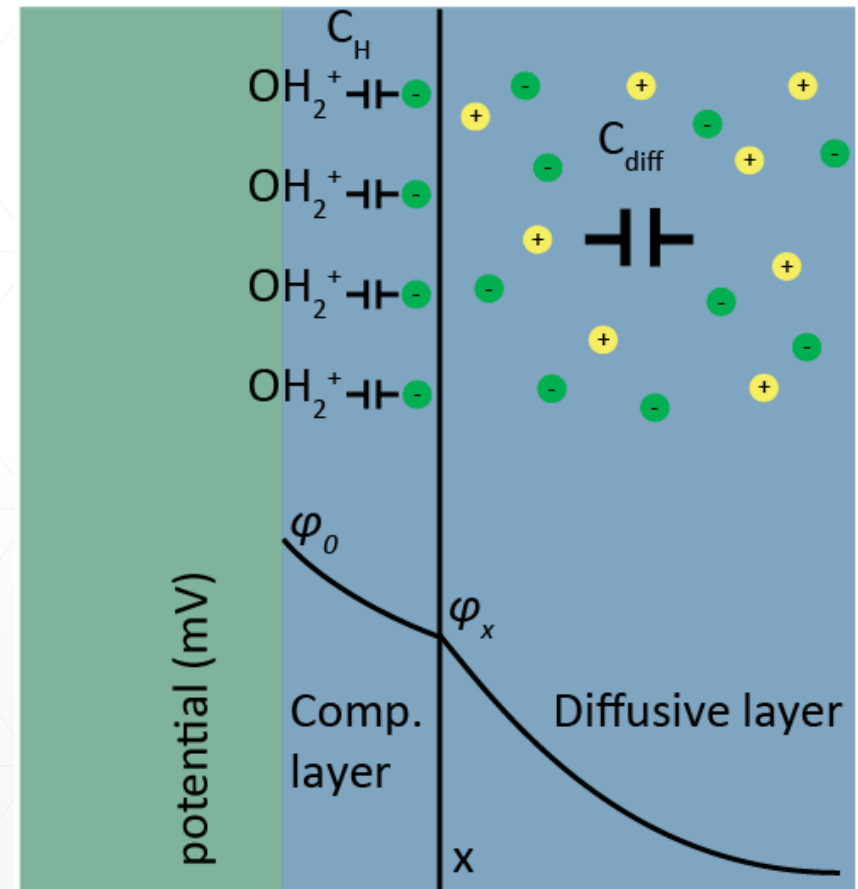
- Difference in proton density between surface and bulk solution
- Surface charges modulate surface potential φ_0 :

$$[H^+]_{\text{surface}} = [H^+]_{\text{bulk}} e^{-\frac{q\varphi_0}{k_B T}}$$

- Change in φ_0 with pH:

$$\frac{\partial \varphi_0}{\delta \text{pH}_{\text{bulk}}} = \ln 10 \frac{k_B T}{q}$$

- At room temperature $\sim 59 \text{ mV/pH}$





ISFET signal to noise ratio

- Signal to noise ratio:

$$SNR = \frac{\langle i_s^2 \rangle}{\langle i_n^2 \rangle + \langle i_x^2 \rangle} = \frac{\delta\varphi_o^2}{\frac{e^2 N_0}{C^2 A} \cdot \frac{\Delta f}{f} + \langle i_x^2 \rangle} / g_m^2$$

- For large g_m ,

$$SNR \approx \frac{C^2 A}{e^2 N_0} \cdot \frac{f}{\Delta f} \cdot \delta\varphi_o^2$$

- Maximize SNR:

$\mu_{FET} \uparrow$

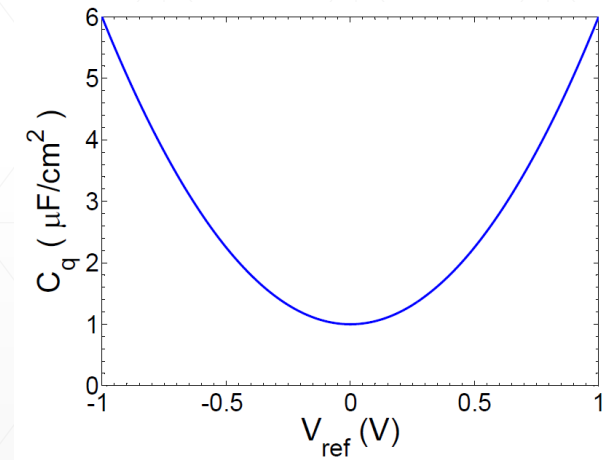
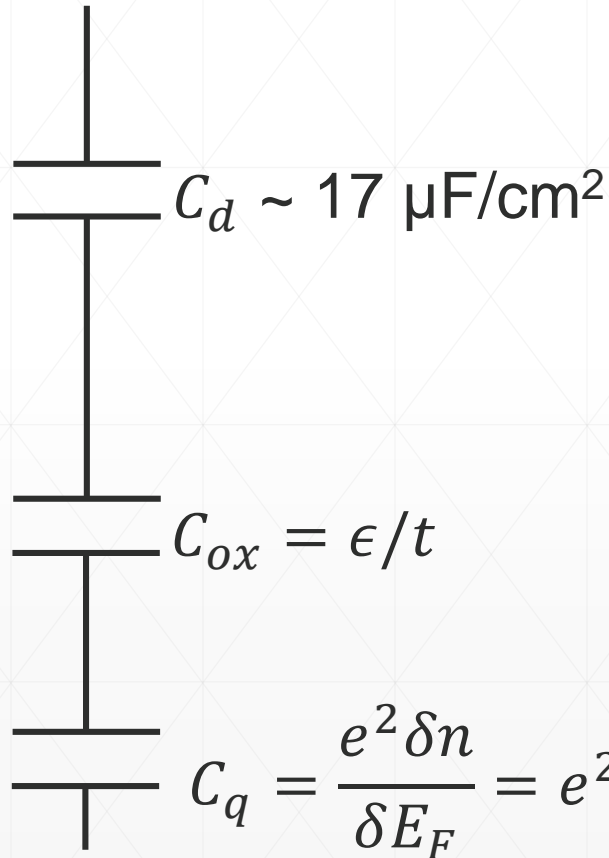
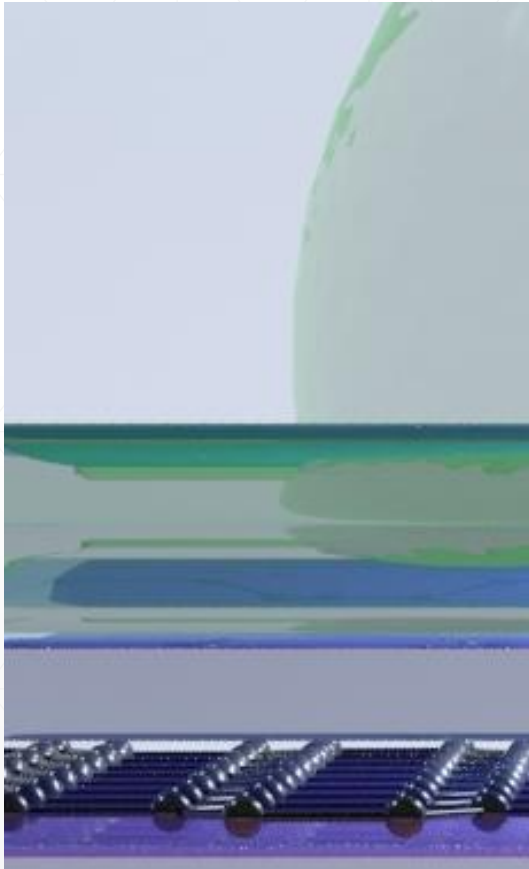
$C \uparrow$

$A \uparrow$



Capacitance of ISFET

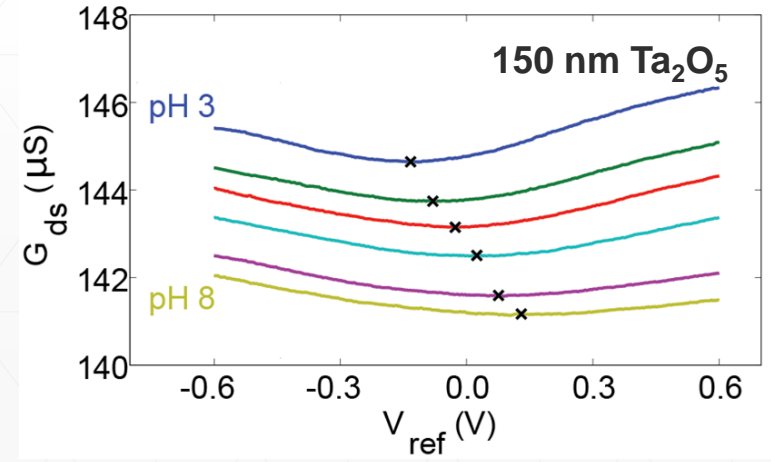
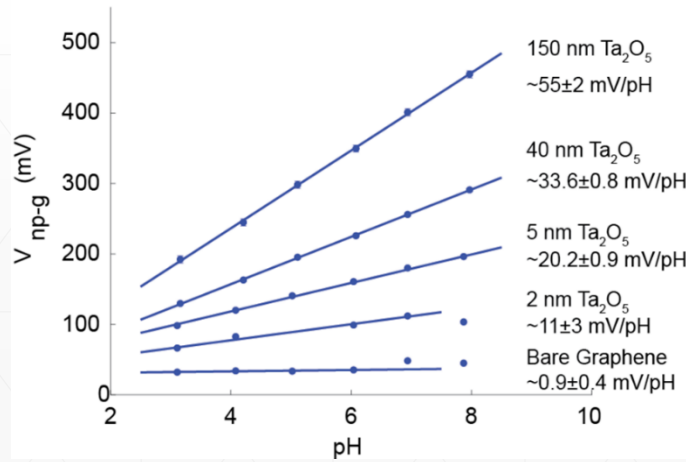
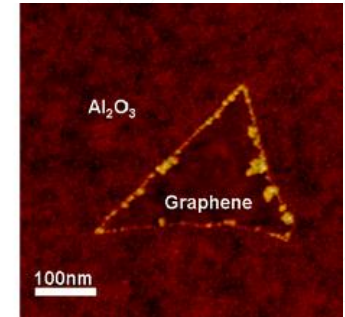
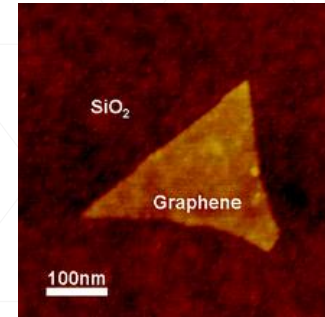
- Capacitance C is a series combination of:





Challenges with Graphene FETs

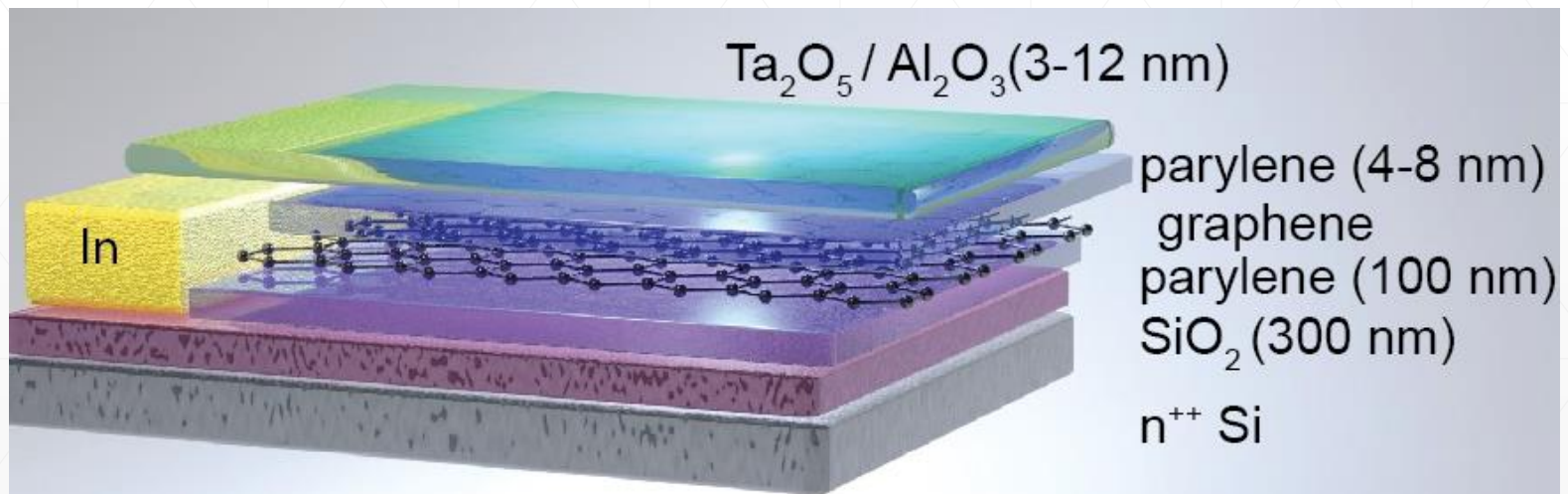
- Difficult to grow stoichiometric oxides on graphene with ALD
- Mobility $\sim 250 \text{ cm}^2/\text{Vs}$
- Capacitance $< 0.1 \mu\text{F}/\text{cm}^2$





Encapsulating graphene with parylene

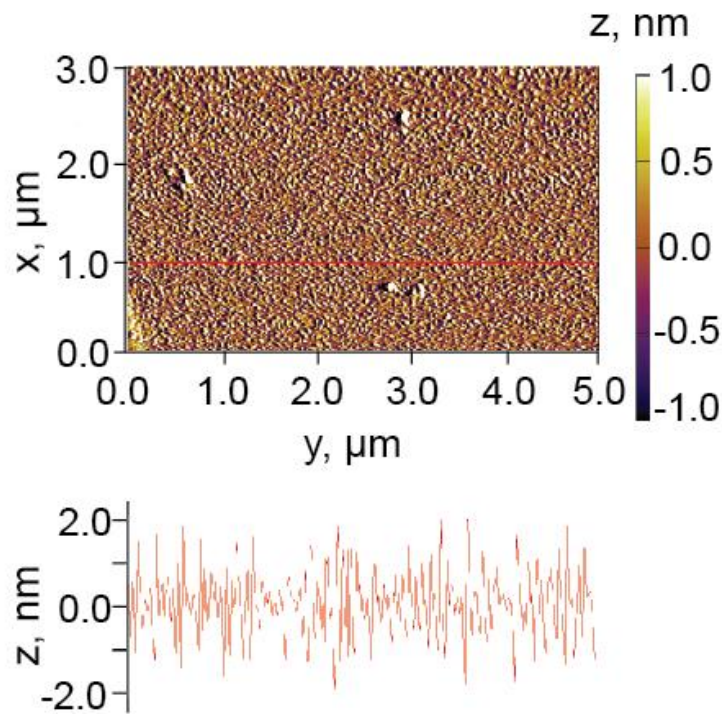
- 4 – 8 nm of parylene is grown on the graphene using CVD
- Protects the graphene during ALD
- Acts as a seeding layer for oxide pre-cursor
- High quality 3nm oxide with uniform coverage



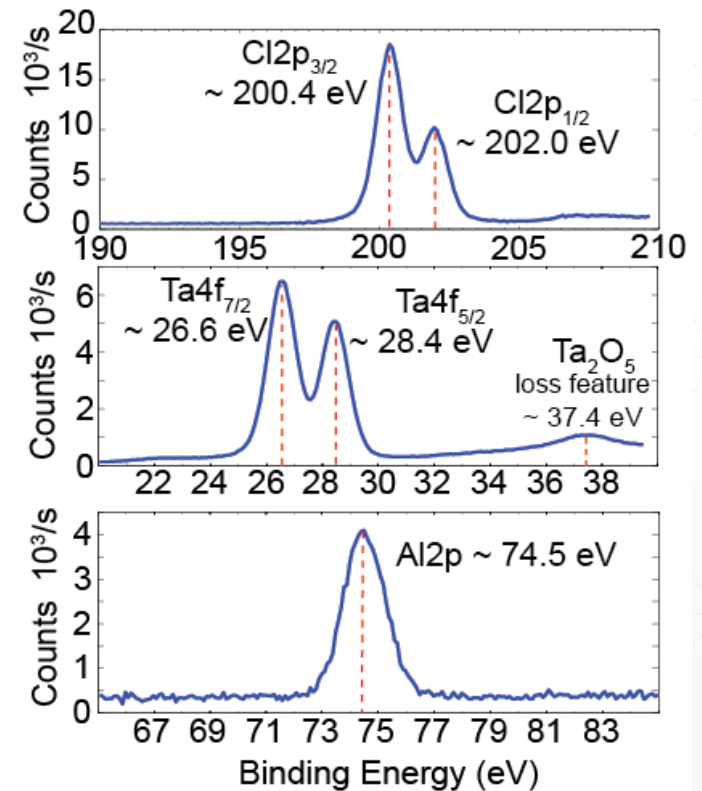
Quality of parylene and metal oxides



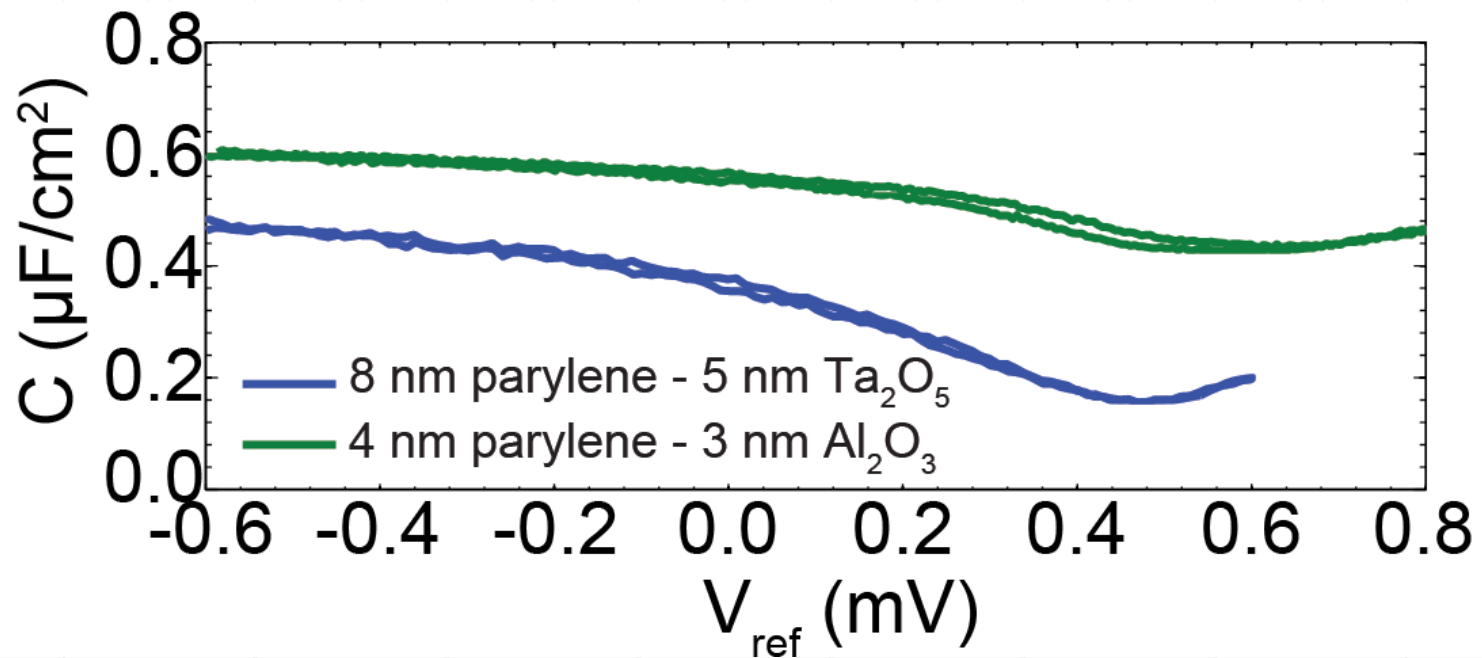
- AFM of 4 nm of parylene



- XPS of parylene and metal oxides



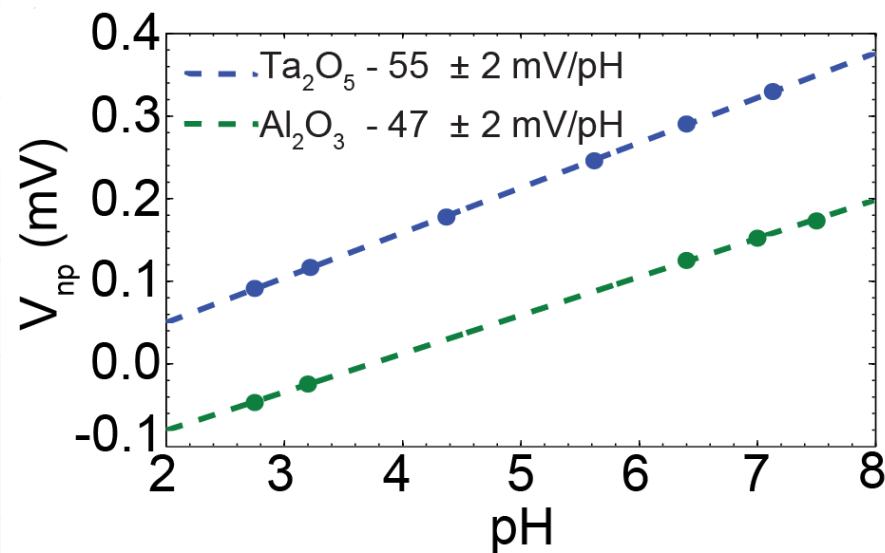
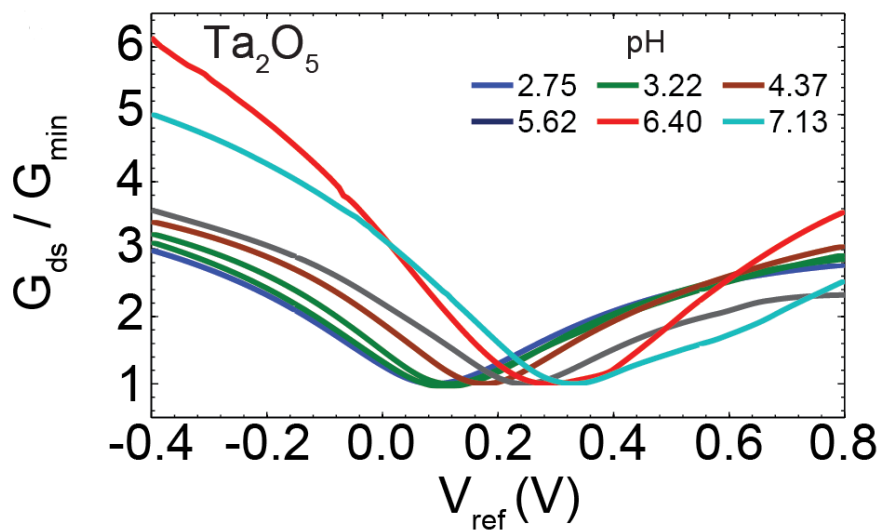
Approaching the quantum capacitance limit





Significant improvements in transconductance and mobilities

- Sensitivities of ~ 55 mV/pH with Ta_2O_5 and ~ 47 mV/pH with Al_2O_3
- Mobilities of $\sim 7,000$ cm^2/Vs

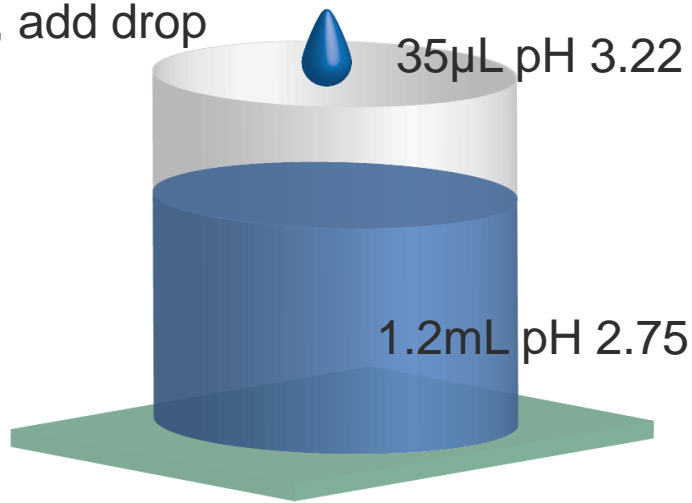




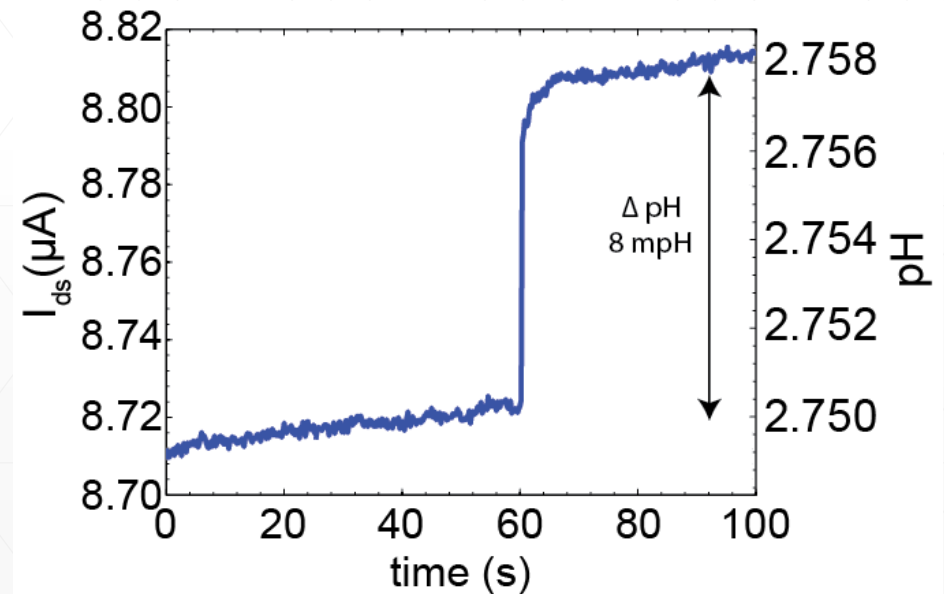
sub mpH Detection Limit

- $\Delta 85 \text{ nA}$ corresponds to $\Delta 8 \text{ mpH}$
- Background RMS noise of $\sim 1 \text{ nA}$ \rightarrow Detection limit is 0.1 mpH

t = 60, add drop



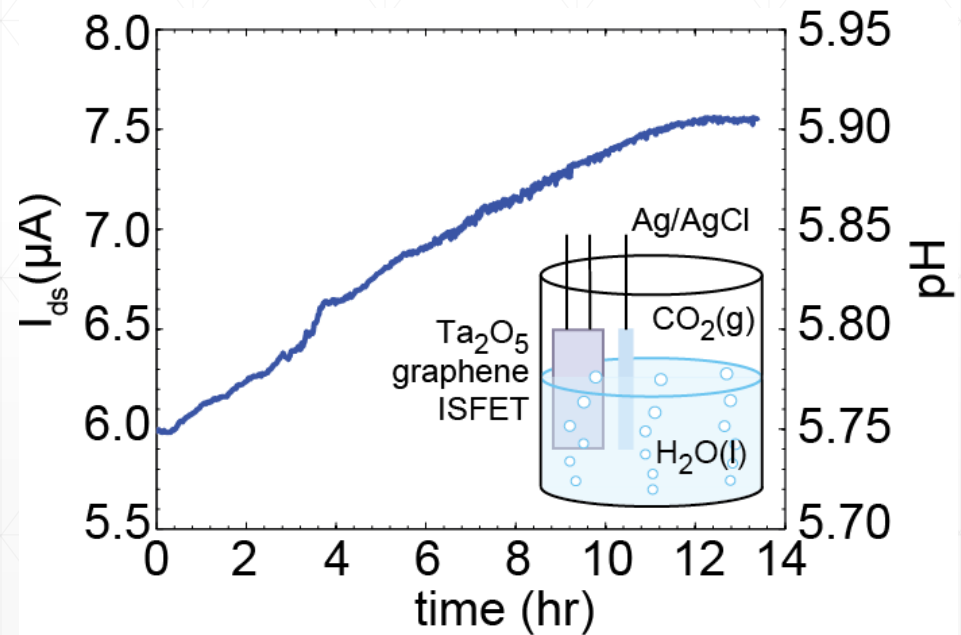
$$\Delta \text{pH} = -\Delta \log([H_3O^+])$$
$$\Delta \text{pH} = 8 \text{ mpH}$$



Monitoring acidity of carbonated water in real time



- 1.2 mL of potable carbonated water with pH = 5.75 over 14 hours





Conclusion and Future Work

- Parylene encapsulation protects graphene from degradation
- Parylene acts as a seeding layer for high quality metal oxide films
- Improved minimum detection limit by 20 times over current sensors
- Other ion and molecules can be measured by replacing the sensing layer

	Detection Limit	Price	Size
Silicon ISFET	2 mpH	\$150 - \$200	~ μm
Glass Electrode	5 mpH	\$300 - \$500	~ mm
Graphene ISFET	0.1 mpH	< \$25 ?	~ mm



Acknowledgments

- *McGill University*
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References

- Bedner K, Guzenko V A, Tarasov A, Wipf M, Stoop R L, Rigante S, Brunner J, Fu W, Davida C, Calame M, Gobrecht J and Schonenberger C 2014 *Sens. Actuators, B* **191** 270-275
- Schedin F, Geim A K, Morozov S V, Hill E W, Blake P, Katsnelson M I and Novoselov K S 2007 *Nat. Mat.* **6** 652-655
- van Hal R, Eijkel J and Bergveld P 1995 *Sens. Actuators, B* **24** 201-205
- Wang X, Tabakman S M and Dai H 2008 *J. Am. Chem. Soc.* **130** 8152-8153
- Fu W, Nef C, Knopfmacher O, Tarasov A, Weiss M, Calame M and Schonenberger C 2011 *Nano Lett.* **11** 3597-3600
- Fakhri I, Sabri S, Mahvash F, Nannini M, Siaj M and Szkopek T 2014 *App. Phys. Lett.* **105**
- Fallahzad B, Lee K, Lian G, Kim S, Corbet C M, Ferrer D A, Colombo L and Tutuc E 2012 *App. Phys. Lett.* **100**
- Levesque P L, Sabri S S, Aguirre C M, Guillemette J, Siaj M, Desjardins P, Szkopek T and Martel R 2011 *Nano Lett.* **11** 132-137
- Sabri S S, Levesque P L, Aguirre C M, Guillemette J, Martel R and Szkopek T 2009 *Appl. Phys. Lett.* **95**
- Fang T, Konar A, Xing H and Jena D 2007 *Appl. Phys. Lett.* **91**(9) 092109
- Xia J, Chen F, Li J and Tao N 2009 *Nat. Nanotechnol.* **4** 505-509



ISFET Operation

The drain current I_{DS} for an ISFET in non-saturation mode is identical to that of a MOSFET :

$$I_{DS} = \frac{\mu C_{ox} W}{L} [(V_{GS} - V_t)V_{DS} - \frac{1}{2} V_{DS}^2]$$

where C_{ox} is the oxide capacitance per unit area, W and L the width and the length of the channel, respectively, and μ is the electron mobility of the channel.



V_t for a MOSFET:

$$V_t = \frac{\Phi_M - \Phi_{Si}}{q} - \frac{Q_{ox} + Q_{SS} + Q_B}{C_{ox}} + 2\phi_f$$

V_t for a ISFET:

$$V_t = E_{ref} - \Psi_0 + \chi^{sol} - \frac{\Phi_{Si}}{q} - \frac{Q_{ox} + Q_{SS} + Q_B}{C_{ox}} + 2\phi_f$$



The Differential Double Layer

Surface charges modulate surface potential φ_0 :

$$[H^+]_{surface} = [H^+]_{bulk} e^{-\frac{q\psi_0}{k_B T}}$$

Small changes in $[H^+]_{surface}$ on the surface charge density σ_0

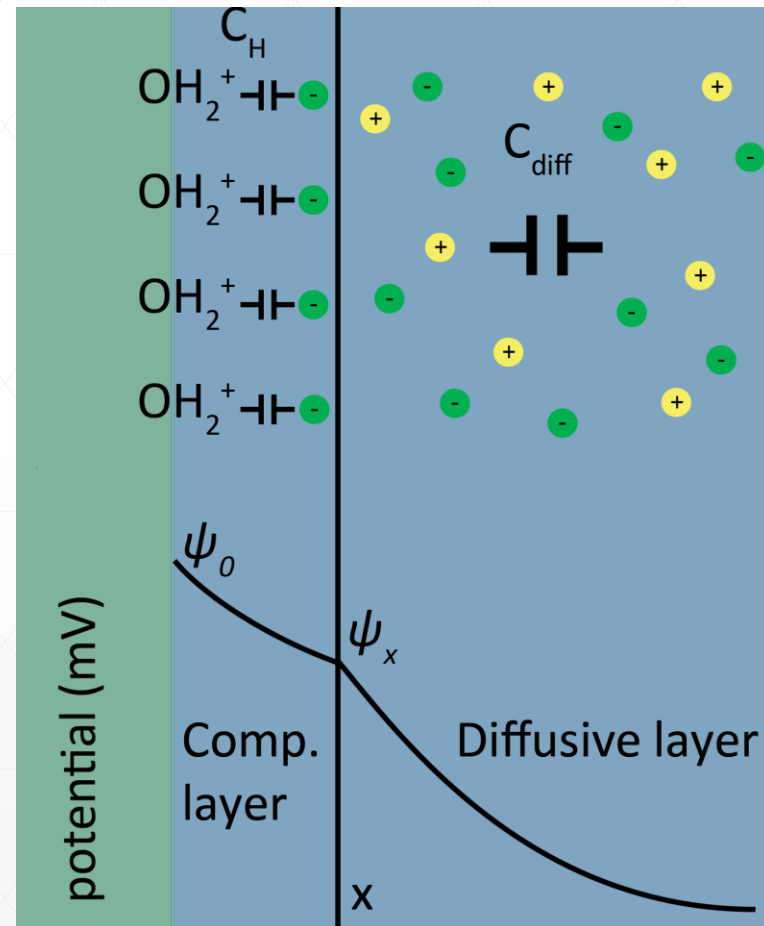
$$\frac{\partial \sigma_0}{\partial \text{pH}_S} = -q\beta_{int}$$

σ_0 is balanced out by charges σ_d in electrolyte

$$\sigma_0 = -\sigma_d = C_d \psi_0 \text{ where } C_d = \frac{C_H C_{diff}}{C_H + C_{diff}}$$

So,

$$\frac{\partial \psi_0}{\partial \text{pH}_S} = \frac{\partial \psi_0}{\partial \sigma_0} \frac{\partial \sigma_0}{\partial \text{pH}_S} = -\frac{q\beta_{int}}{C_d}$$





Sensitivity factor α

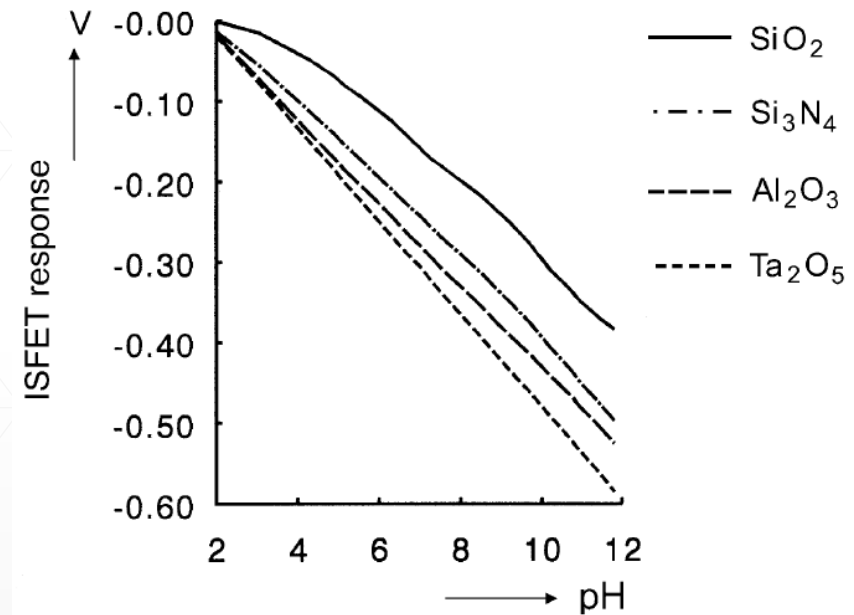
- The sensitivity of ISFETs are a fraction of the Nernstian limit:

$$\frac{\partial \varphi_0}{\delta pH_{bulk}} = \alpha \ln 10 \frac{k_B T}{q}$$

- ISFET sensitivity factor α :

$$\alpha = 1 / \left(1 + \ln 10 \cdot \frac{kT}{q} \cdot \frac{C_d}{q \beta_{int}} \right)$$

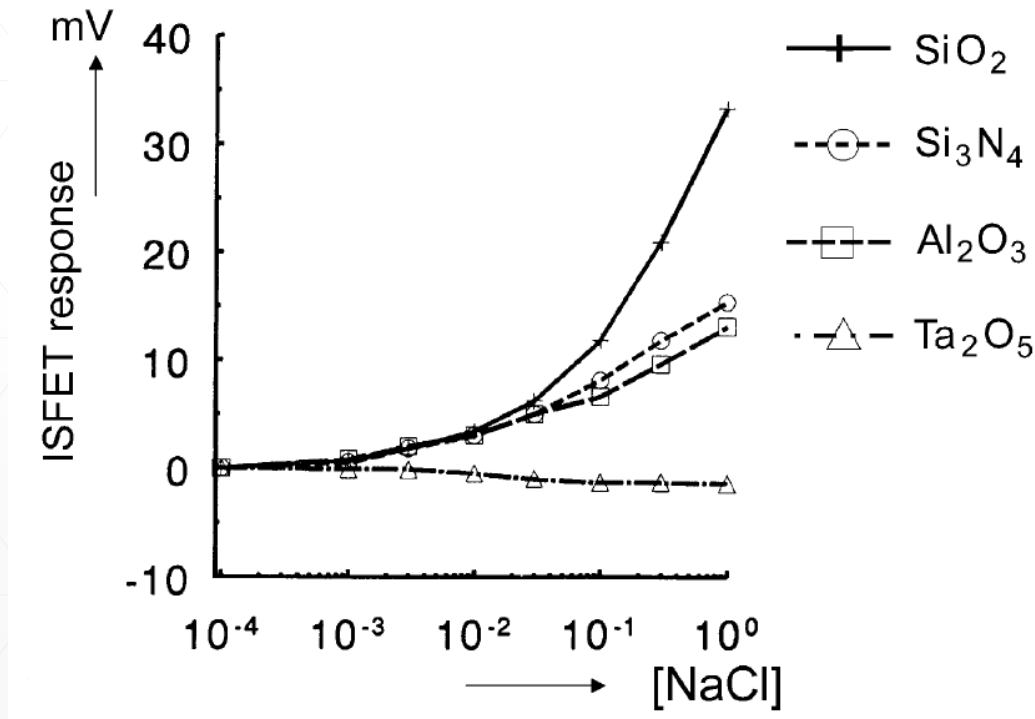
- Ta_2O_5 $\alpha \sim 0.98$ Al_2O_3 $\alpha \sim 0.84$





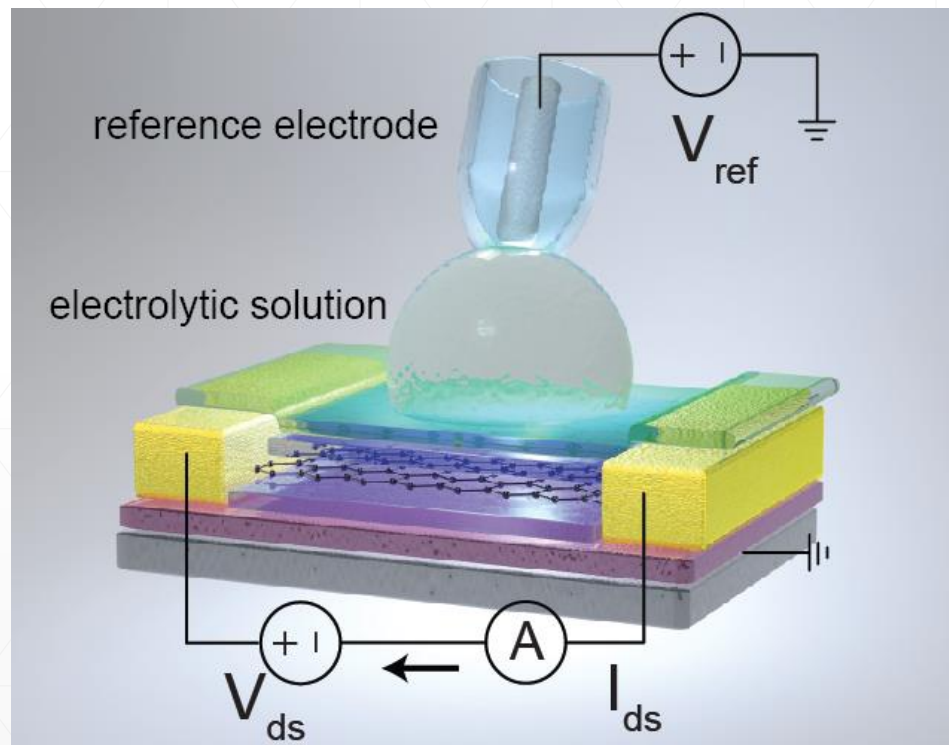
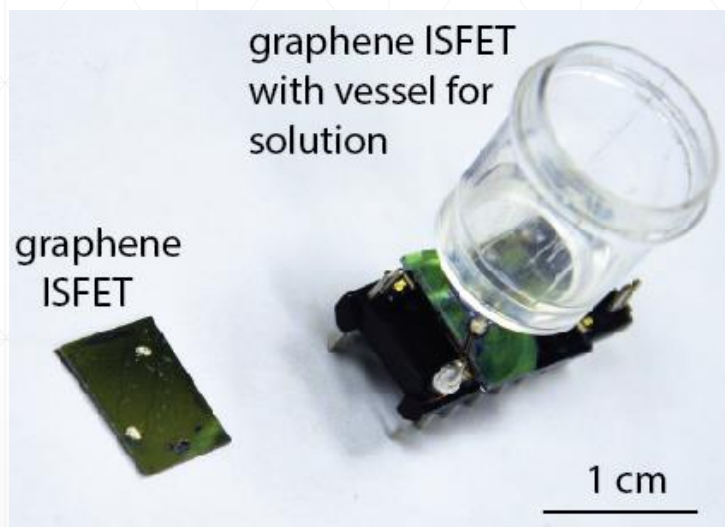
Ta₂O₅ insensitive to other ions

- At a constant pH, Ta₂O₅ exhibits no response to changes in concentrations to other ions.



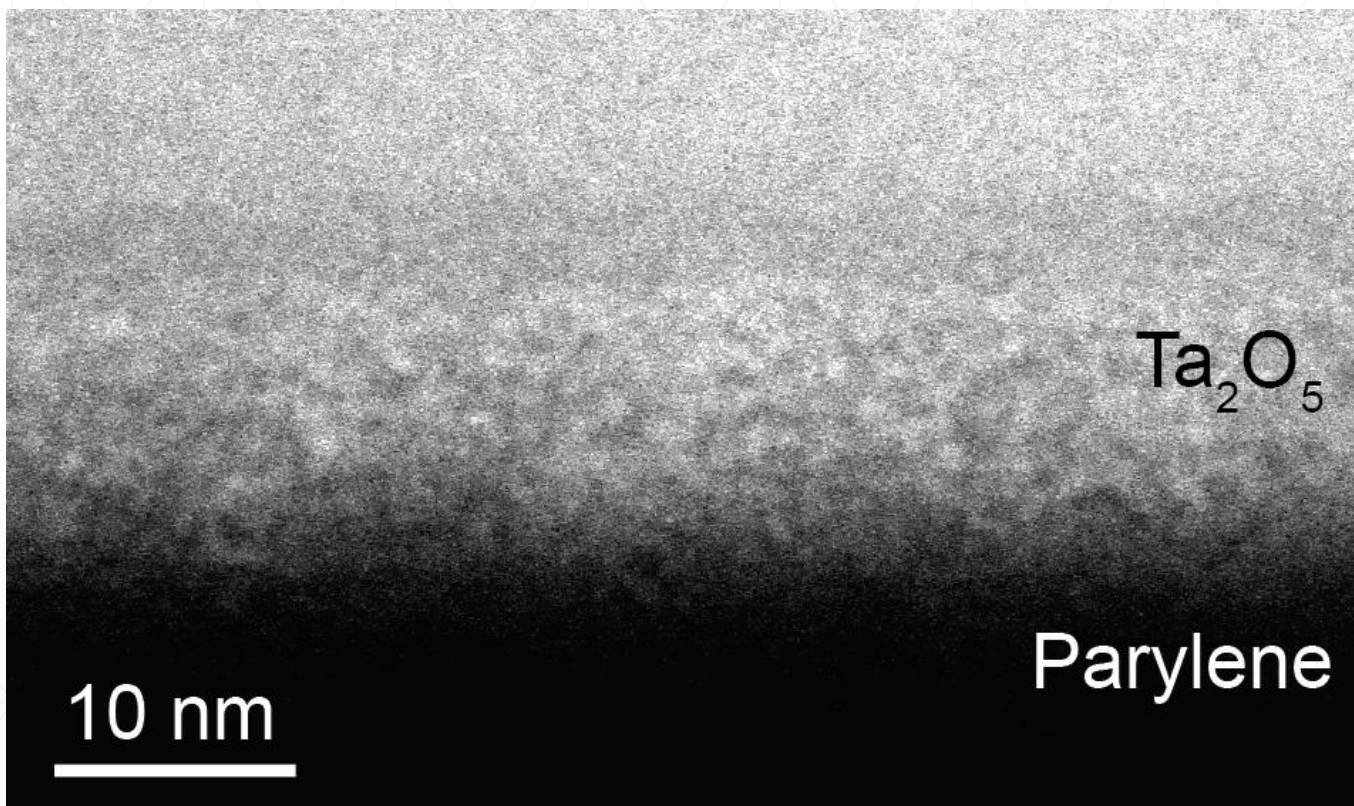


Device Setup





TEM





ISFET signal and noise

- ISFET signal current is $i_s = g_m \times \delta\phi_o$
- Power noise current arises from ISFET $\langle i_n^2 \rangle$ and read-out electronics $\langle i_x^2 \rangle$
- ISFET noise is dominated by charge fluctuation in the sensing layer

$$\langle i_n^2 \rangle = g_m^2 \frac{e^2 N_0}{C A} \cdot \frac{\Delta f}{f}$$



Sources of Noise

- Brownian motion of the ions

$$N_{BN} = 4k_B T \operatorname{Re}(Z)$$

- Fluctuation of dipoles in the oxide

$$N_{DP} = \frac{2k_B T \tan(\delta)}{\pi C} \cdot \frac{1}{f}$$

- Trapping of carriers in defects at the insulator/electrolyte interface

$$N_{CT} = \frac{e^2 N_{trap}}{C^2 W L} \cdot \frac{1}{f}$$

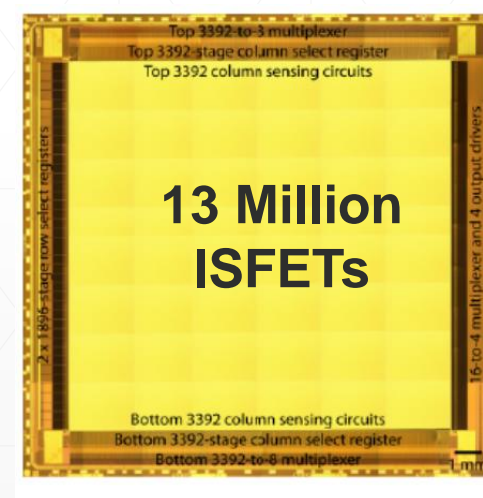
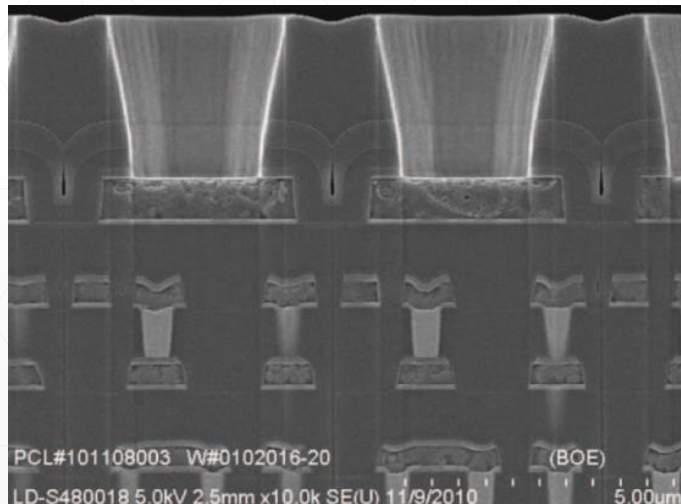
- Thermal fluctuation of electrons in the channel

$$N_{JN} = 4k_B T \gamma / g_m$$



Silicon ISFETs and glass electrode

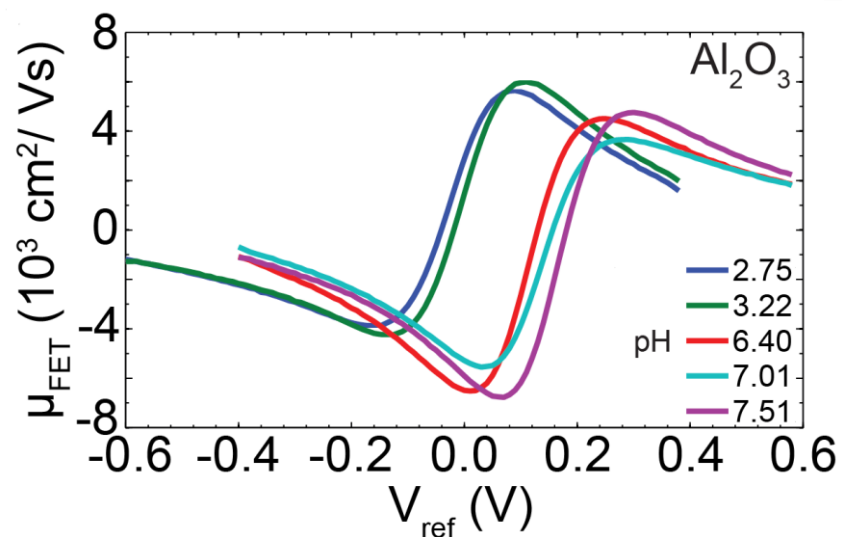
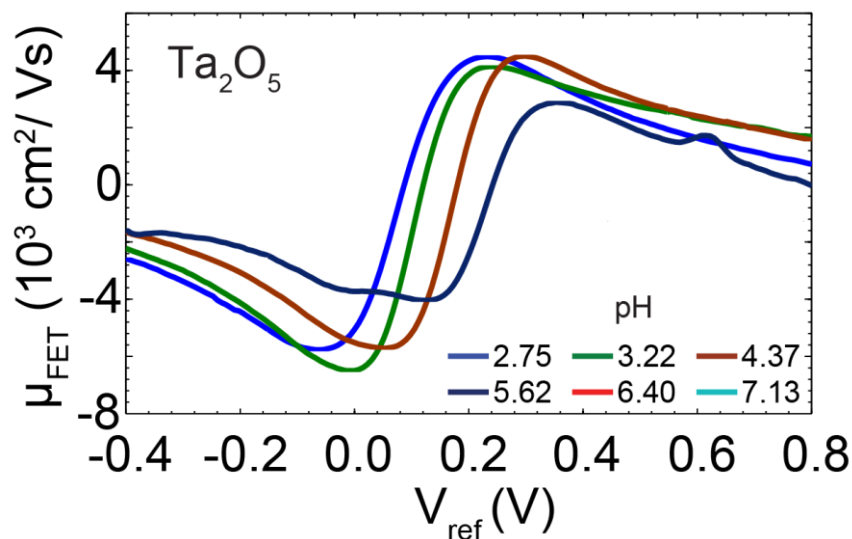
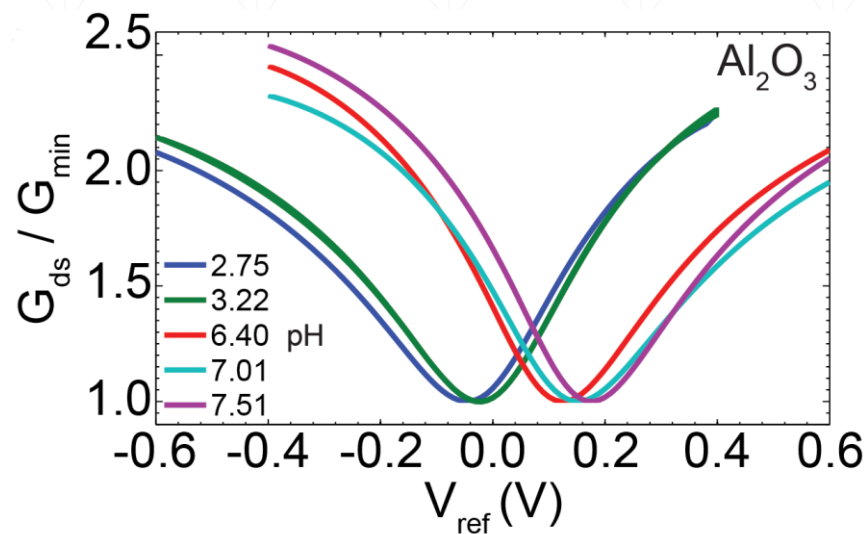
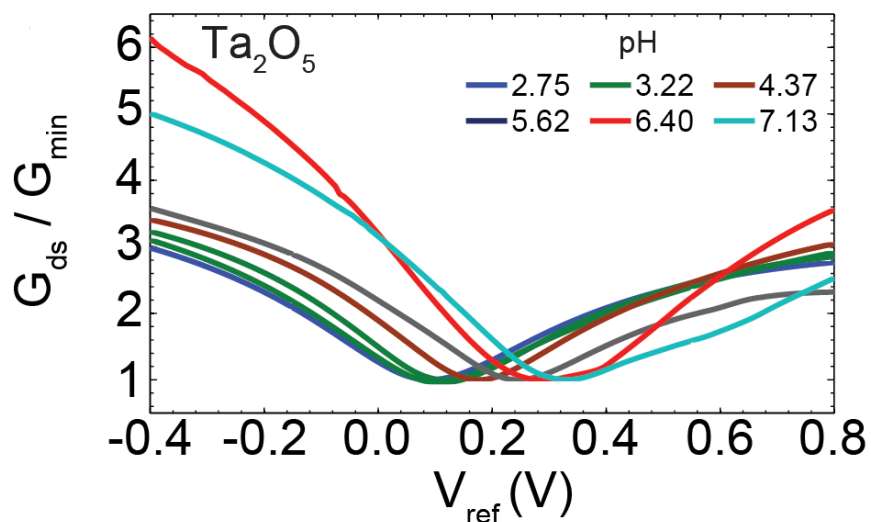
- Fabricated using standard CMOS process
- Ta_2O_5 is grown back end of line (BEOL)
- Detection limit of ~ 20 mpH
- Charge trapping in oxide layers



17.5 mm



pH response and mobility





Time sensitivity and stability

